

Surface morphology of InAs considering entropy effects

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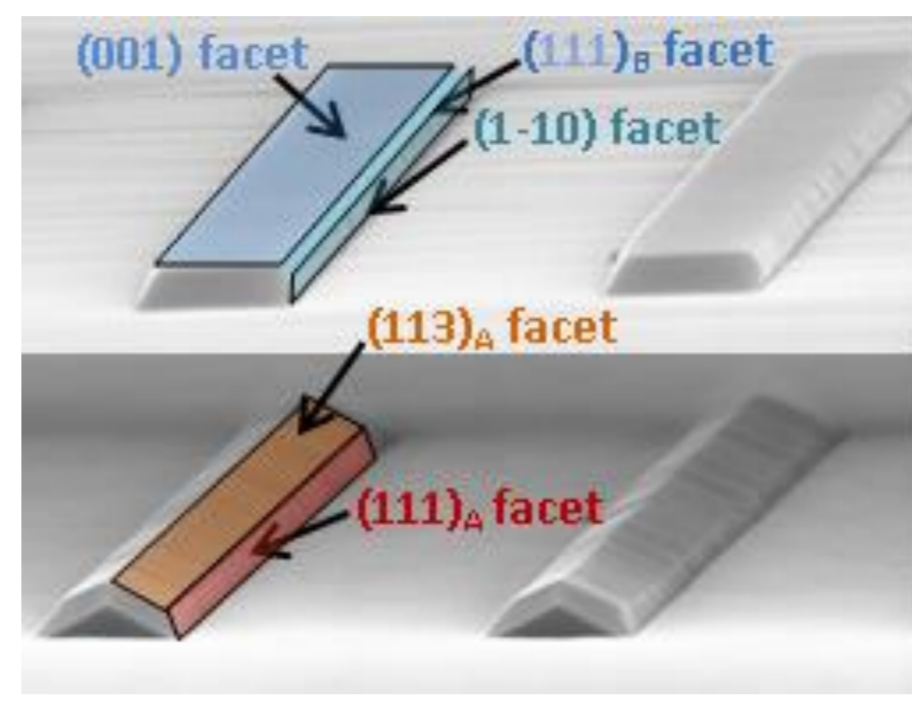
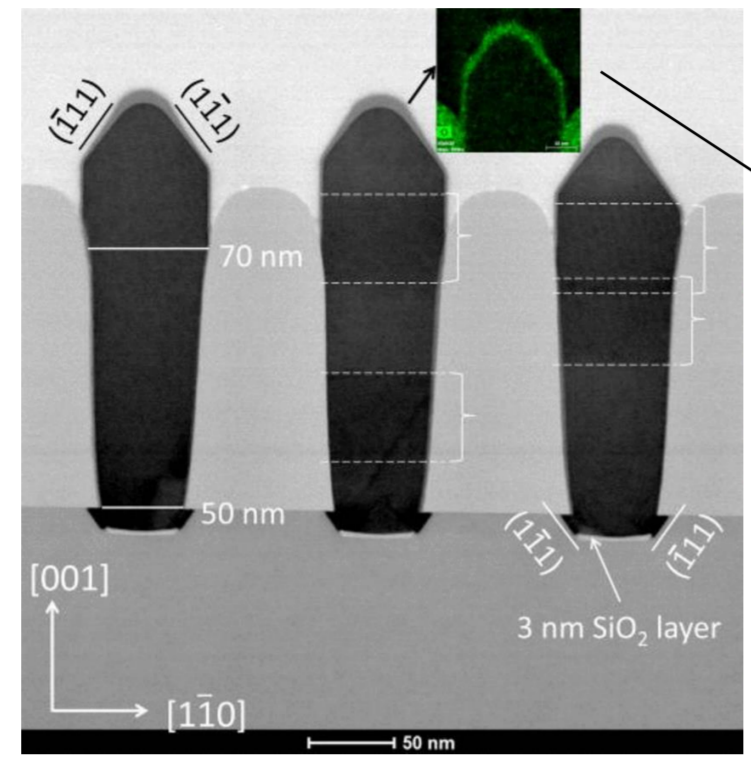
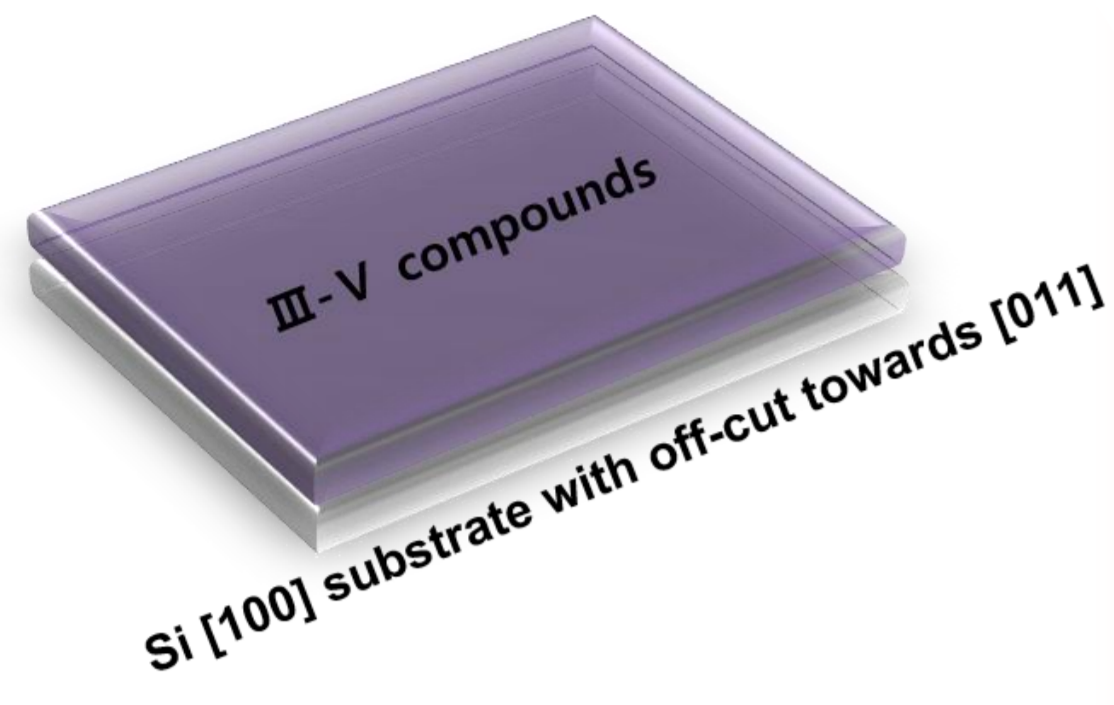
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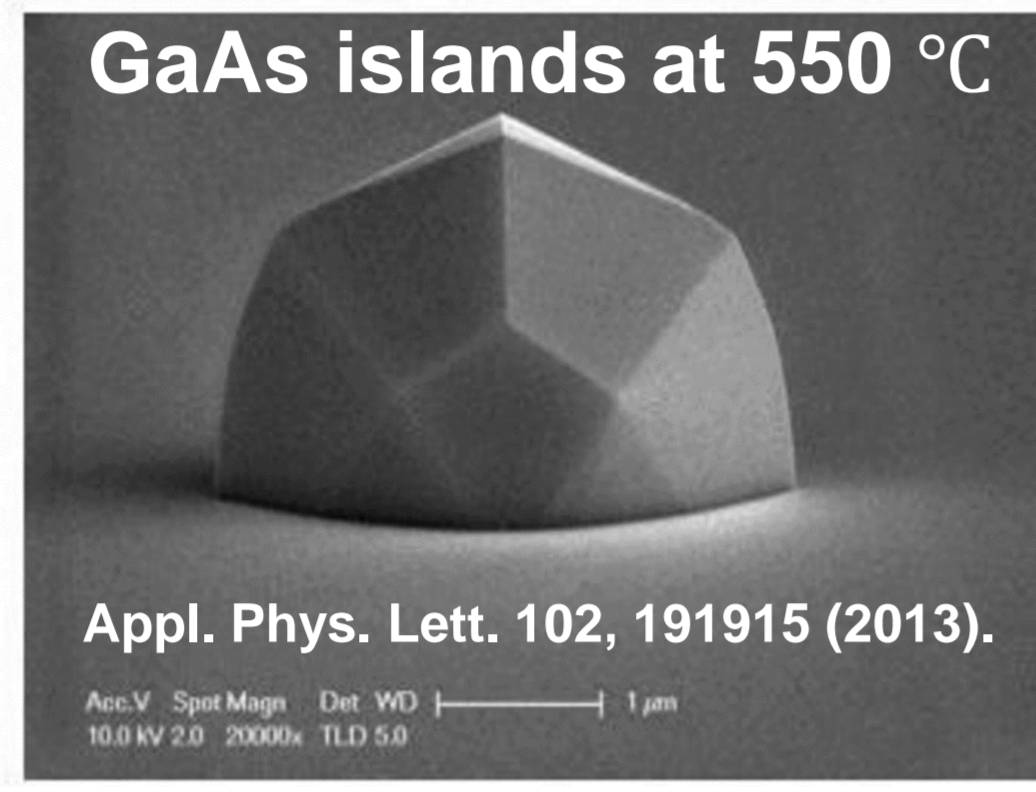
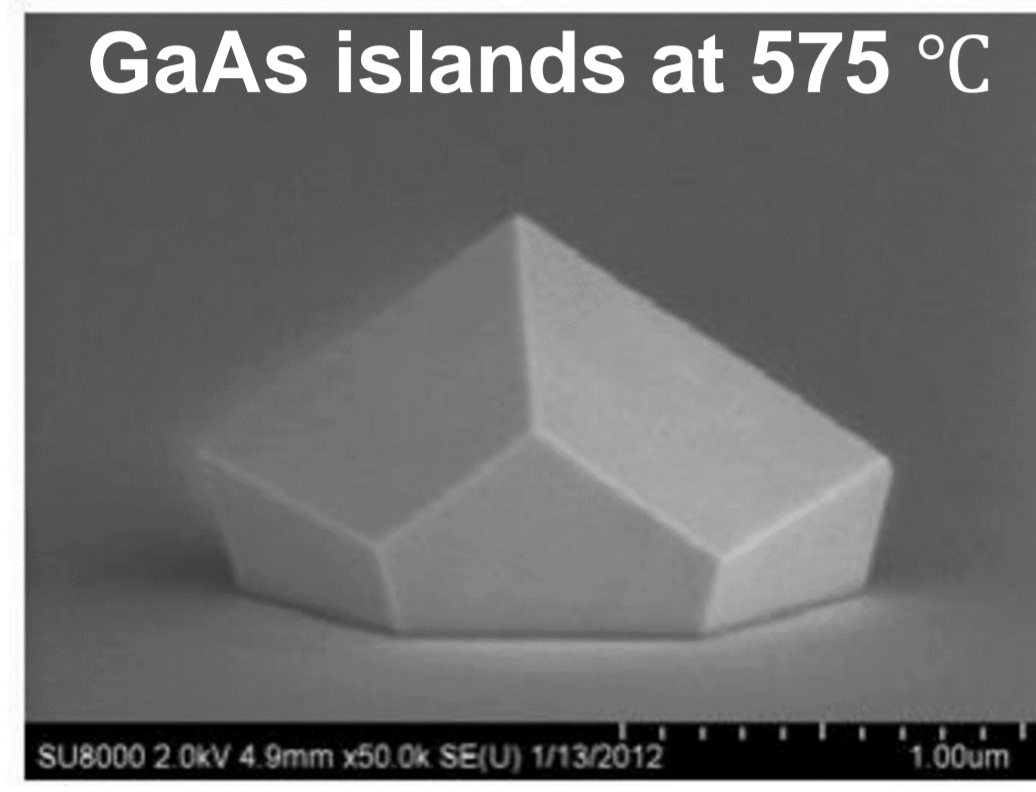
Computational Materials Design

INTRODUCTION

III-V compounds on Si [100] substrate



How can we predict the surface structures and morphology?



- III-V compounds are required to be grown on Si [100] substrate.
- The morphology is composed of some facets with different orientations.
- The surface morphology depends on the environment conditions (T, P).

COMPUTATIONAL DETAILS

Computational details

- VASP (Vienna *ab-initio* Simulation Package)
- xc-functional : LDA-CA
- Cutoff energy : 300 eV
- k-points : G 8×8×8 for the conventional cell of InAs.
- Valence treatment : As=4s²4p³, In=4d¹⁰5s²5p¹
- Vacuum thickness : >10 Å
- The top 5 layers of the total 9 layers were allowed to move.
- The bottom layers were fixed and saturated with hydrogen.

METHODOLOGY

Chemical potential calculation of ideal gas

$$\mu_{As_2}(T, P) = \frac{1}{2} E_{As_2}^{total} + \frac{1}{2} E_{As_2}^{ZPE} + \Delta\mu_{As_2}(T, p^0) + \frac{1}{2} k_B T \ln \frac{p}{p^0}$$

Translation

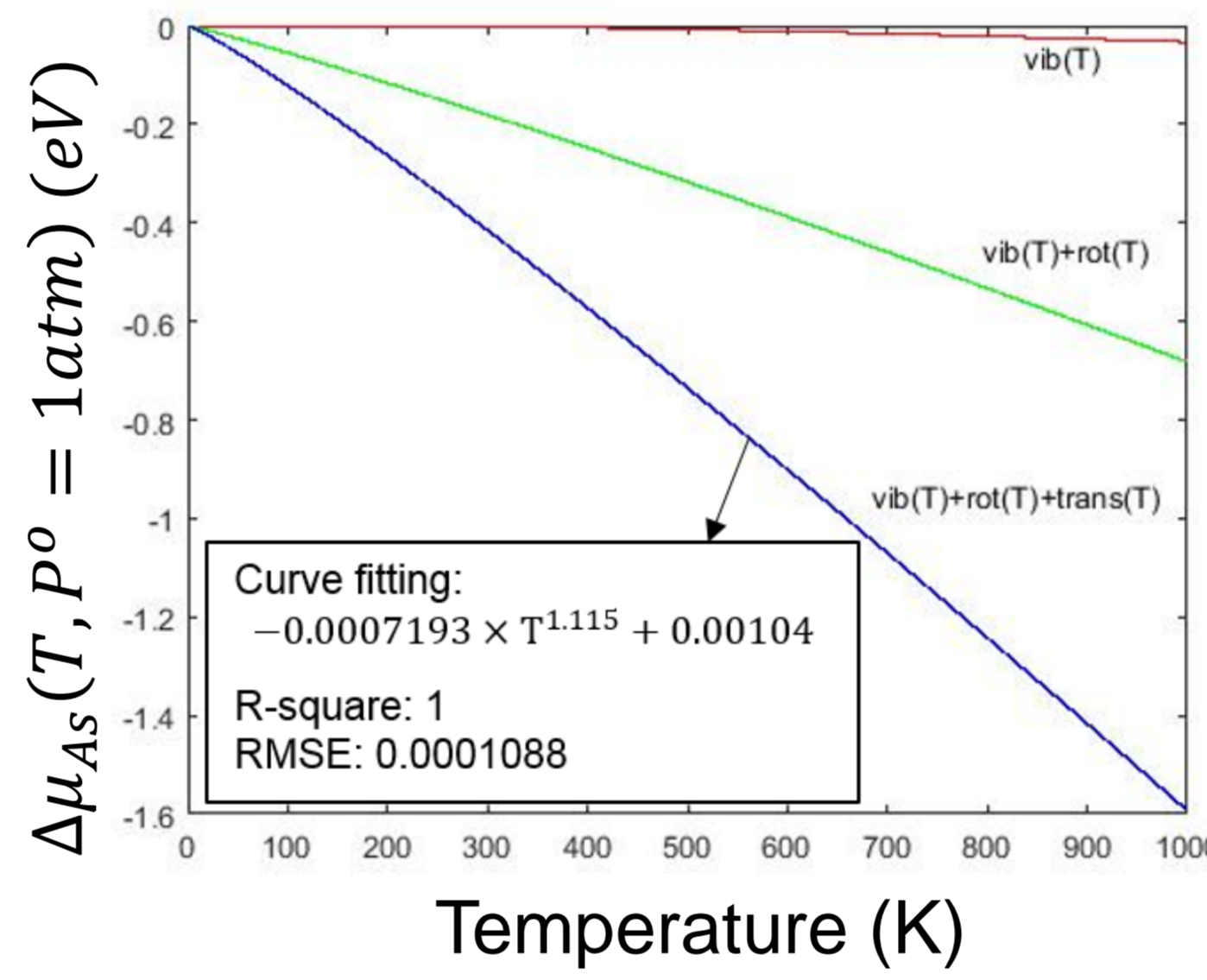
$$\frac{1}{2} \Delta\mu_{As_2}^{trans}(T, p^0) = -\frac{1}{2} k_B T \ln \left[\left(\frac{2\pi m}{h^2} \right)^{\frac{3}{2}} \frac{(k_B T)^{\frac{5}{2}}}{p^0} \right]$$

Rotation

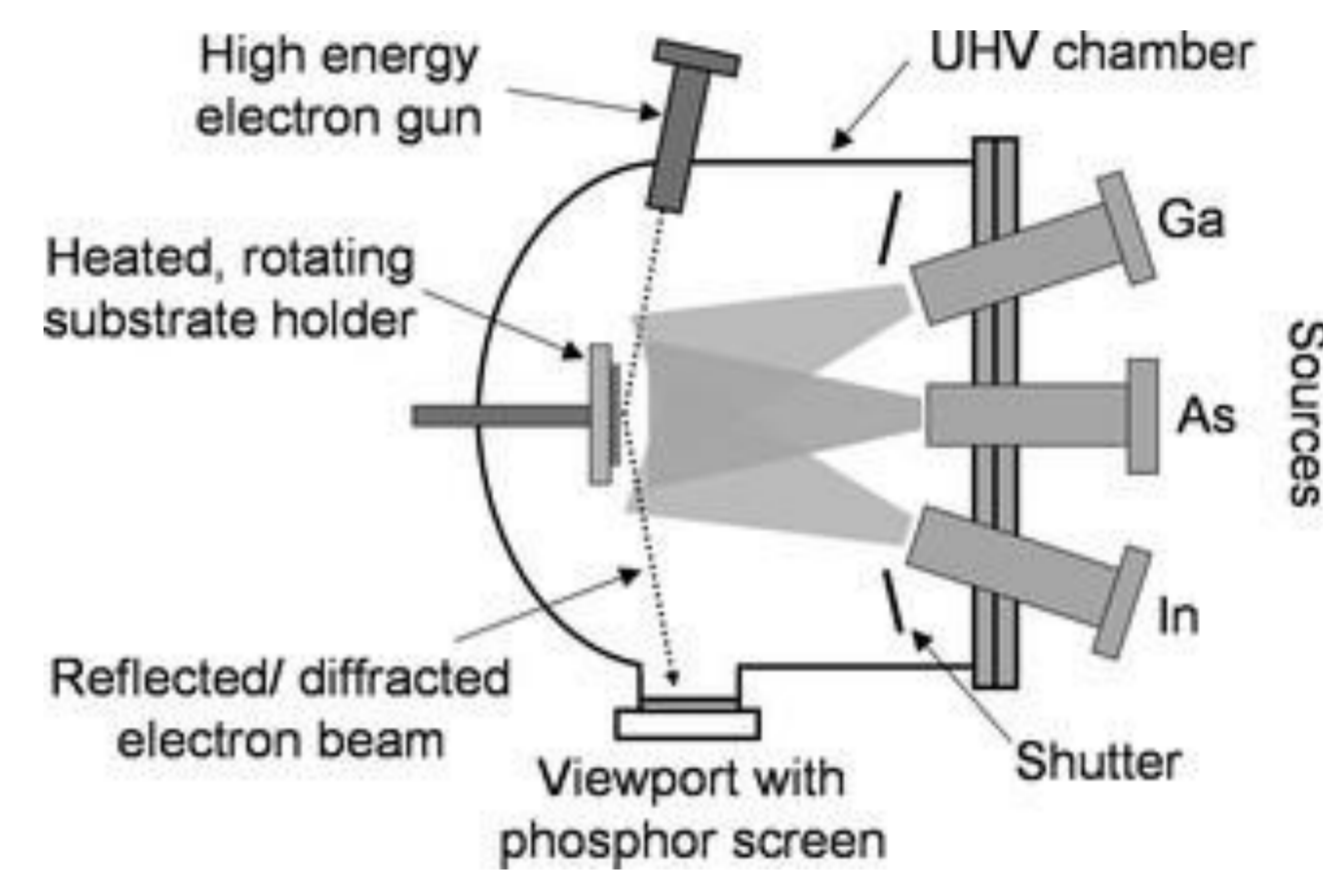
$$\frac{1}{2} \Delta\mu_{As_2}^{rot}(T, p^0) = -\frac{1}{2} k_B T \ln \left(\frac{2Ik_B T}{\sigma_{sym} h^2} \right)$$

Vibration (3N-5=1 mode)

$$\frac{1}{2} \Delta\mu_{As_2}^{vib}(T, p^0) = \frac{1}{2} k_B T \ln \left[1 - \exp \left(-\frac{\hbar\omega_0}{k_B T} \right) \right]$$

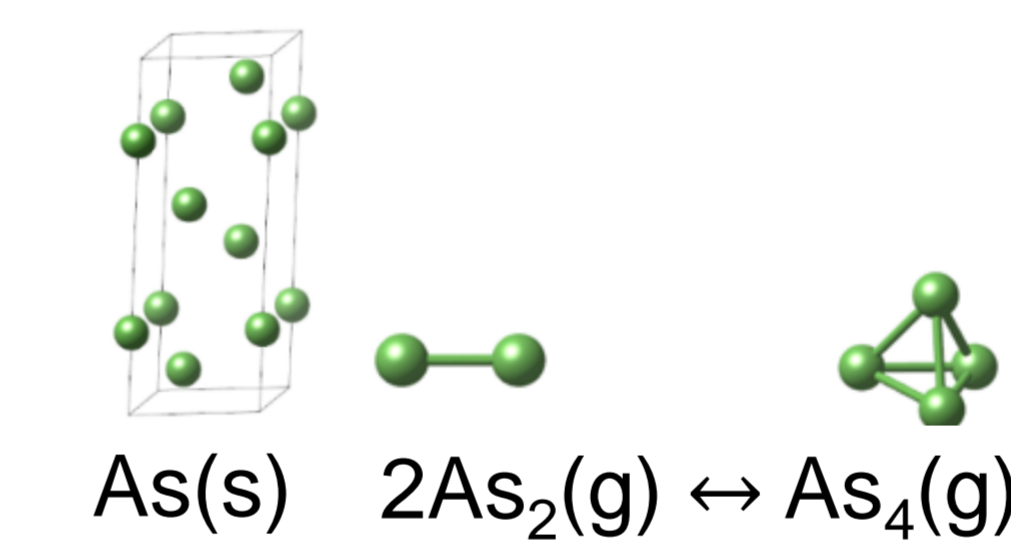


Arsenic as reservoir in Molecular Beam Epitaxy chamber

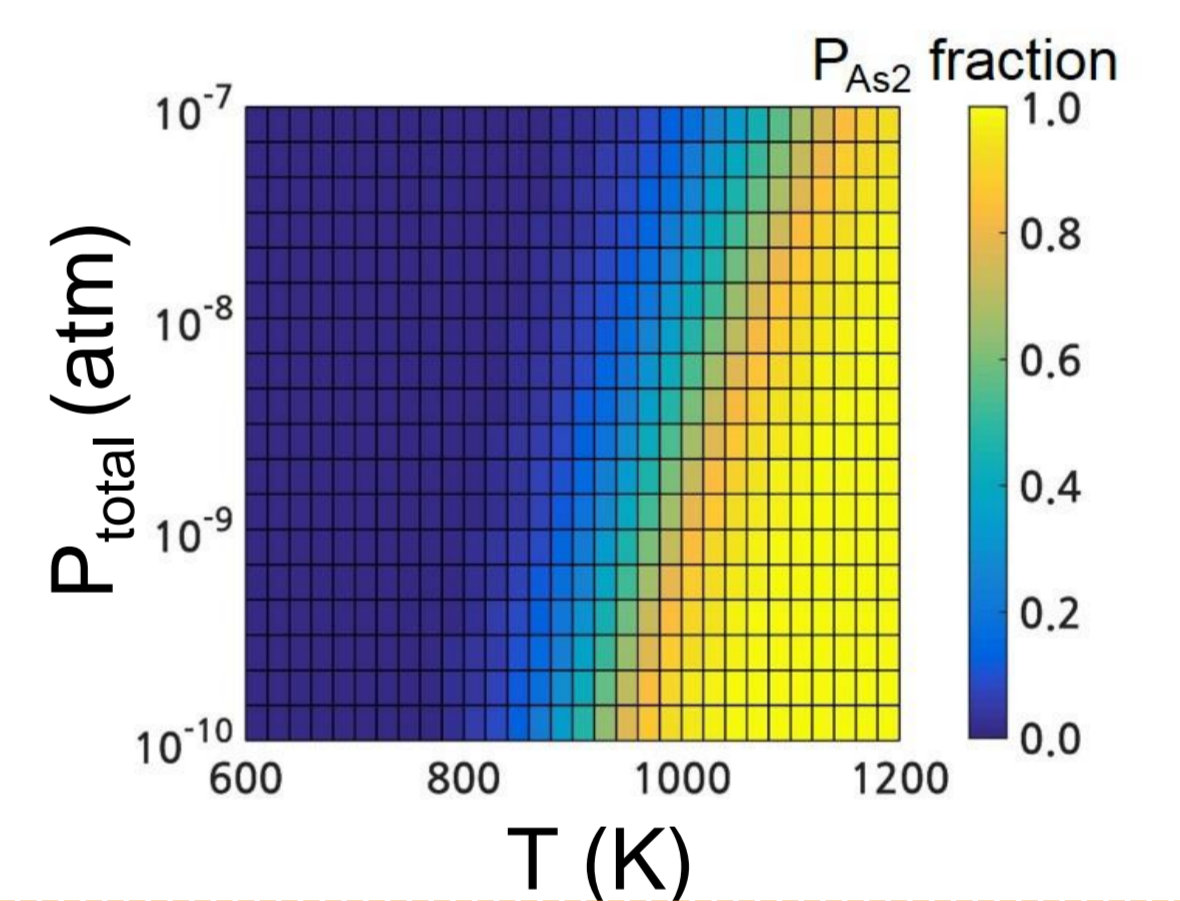


High Vacuum
In: from 1×10⁻¹⁰ to 2×10⁻¹⁰ atm
As: from 3×10⁻⁸ to 3×10⁻⁹ atm

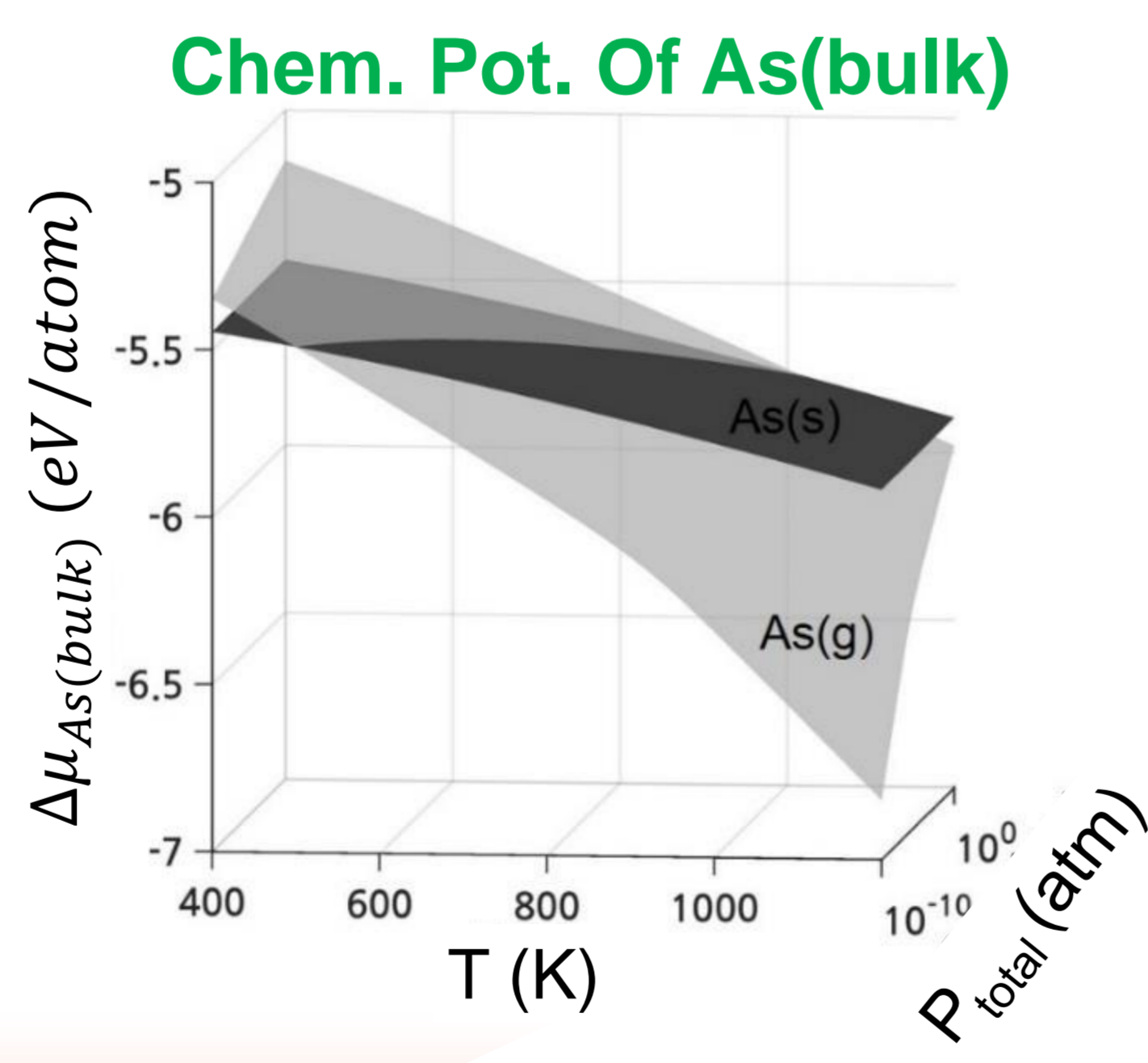
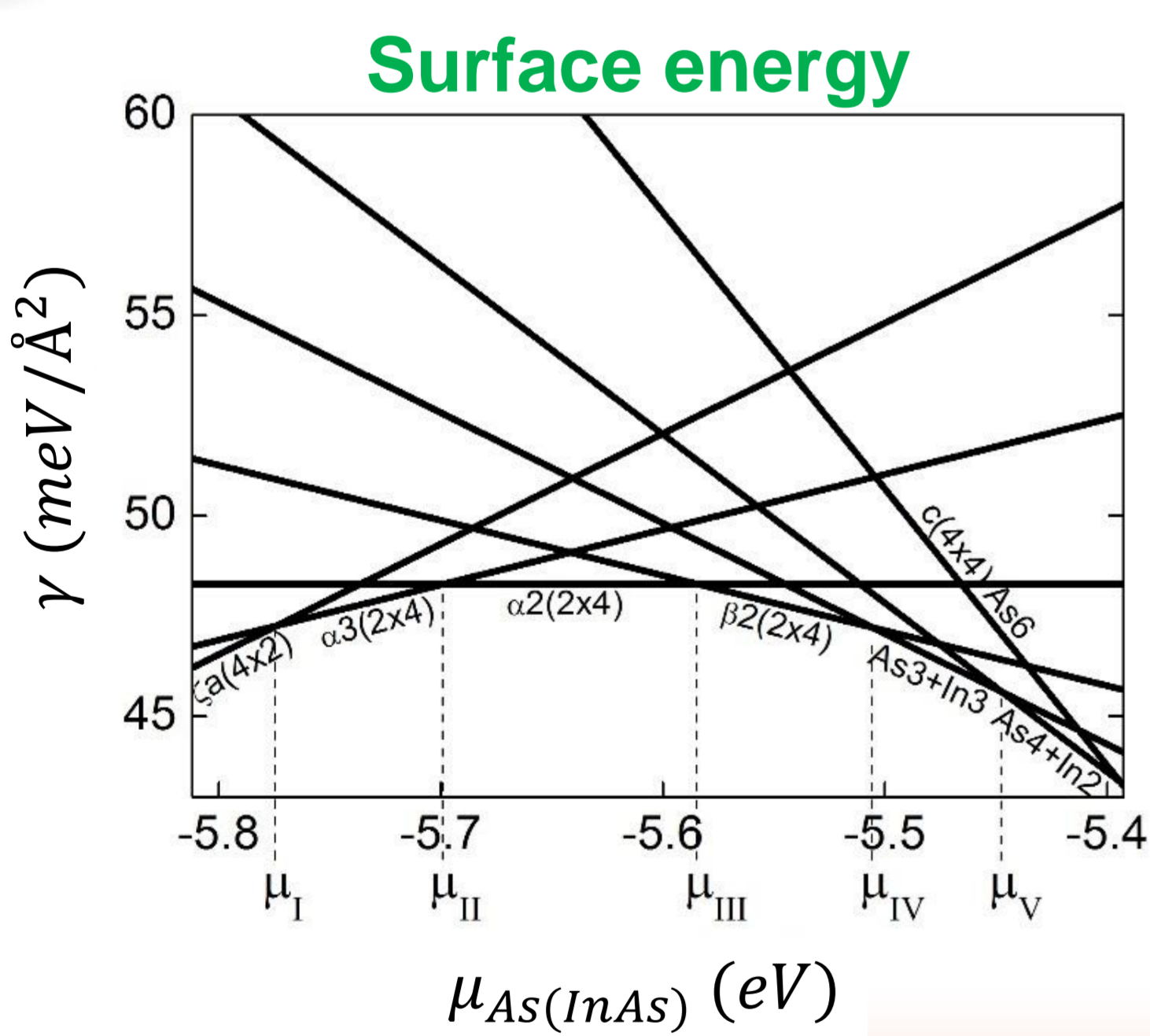
As(bulk) as reservoir in equilibrium with InAs surface, $\mu_{As(bulk)} = \mu_{As(InAs)}$



$$P_{As_2} + P_{As_4} = P_{total}$$

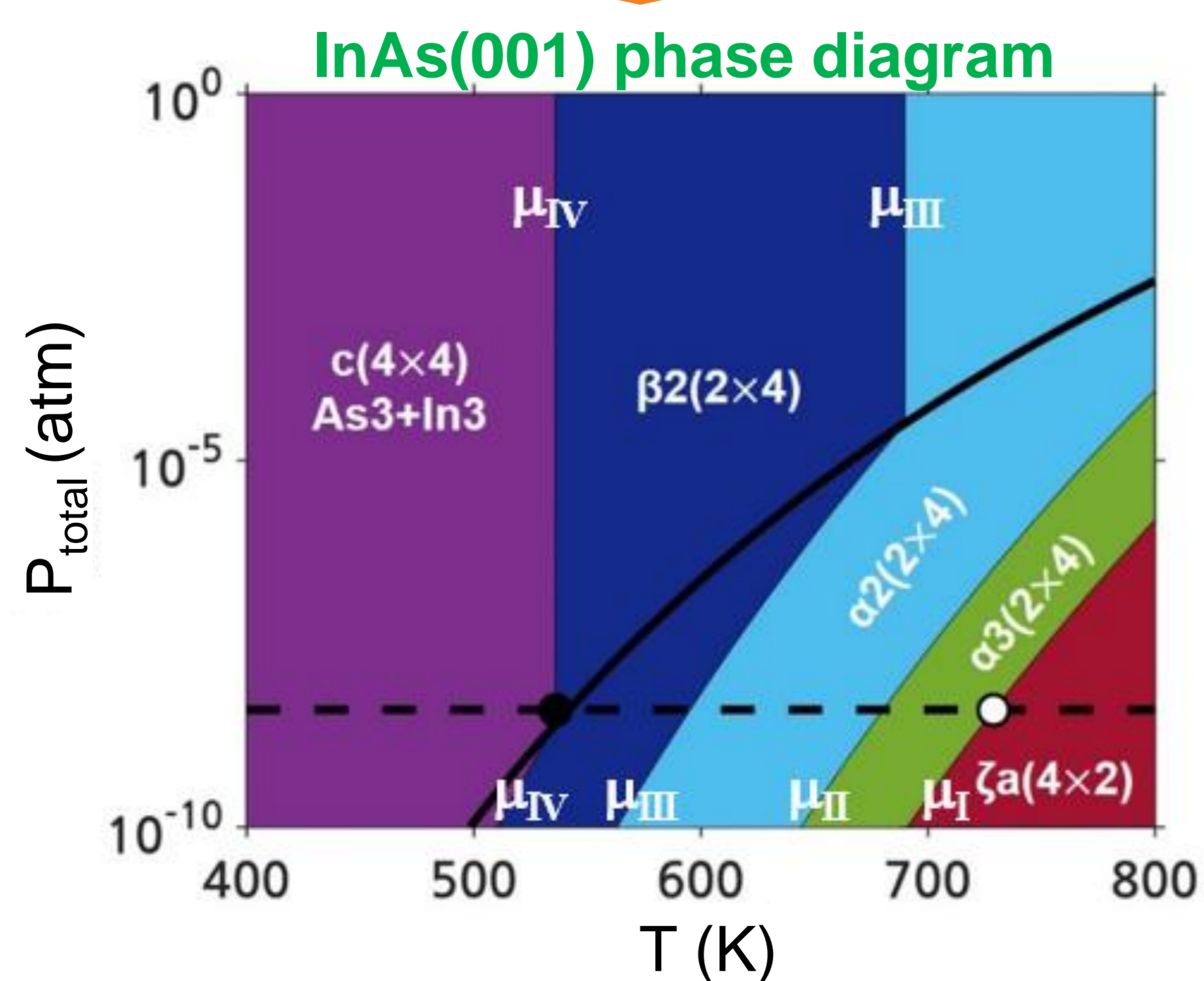


Results & discussions

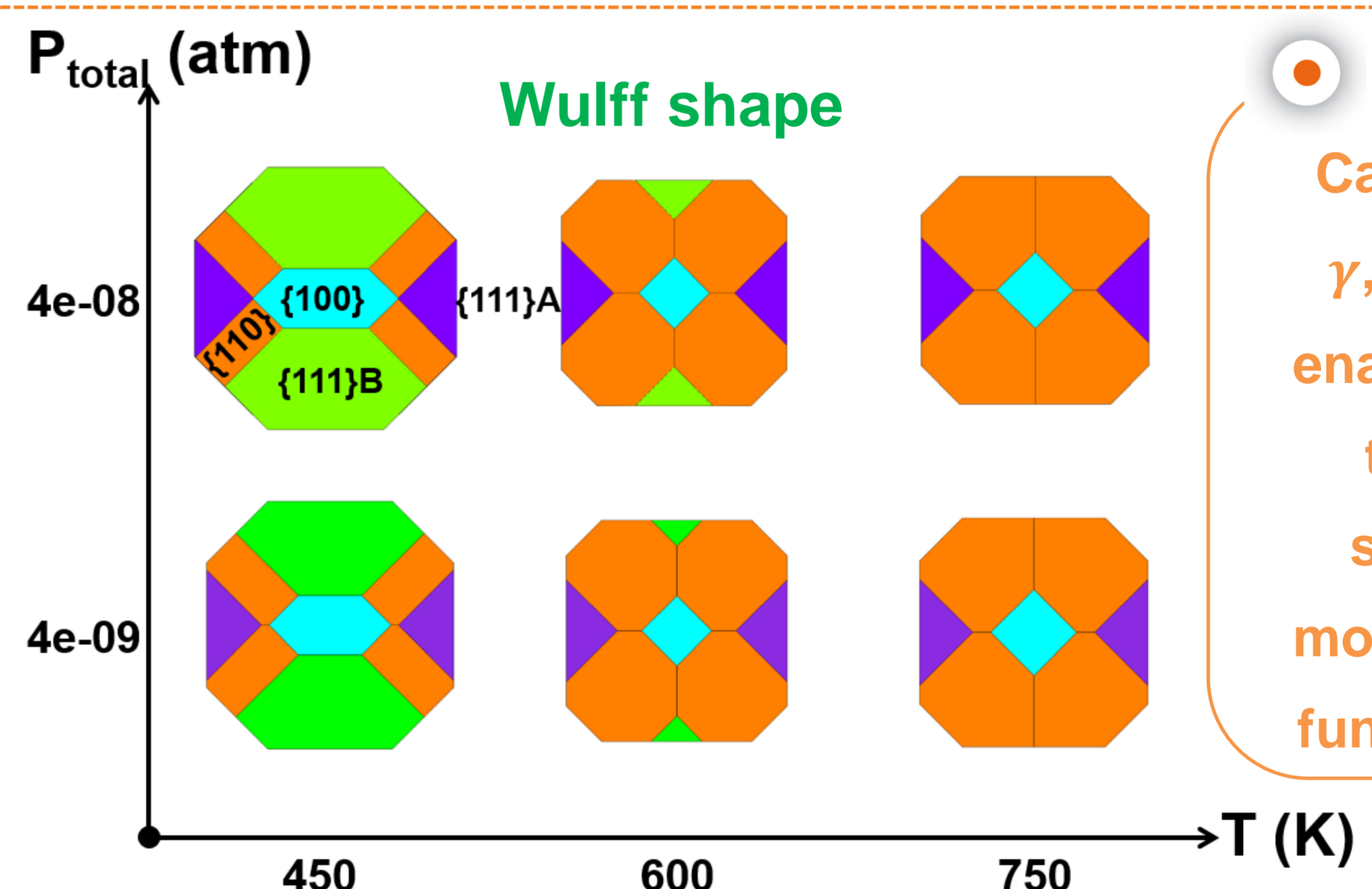


Equilibrium condition,

$$\mu_{As(bulk)} = \mu_{As(InAs)}$$



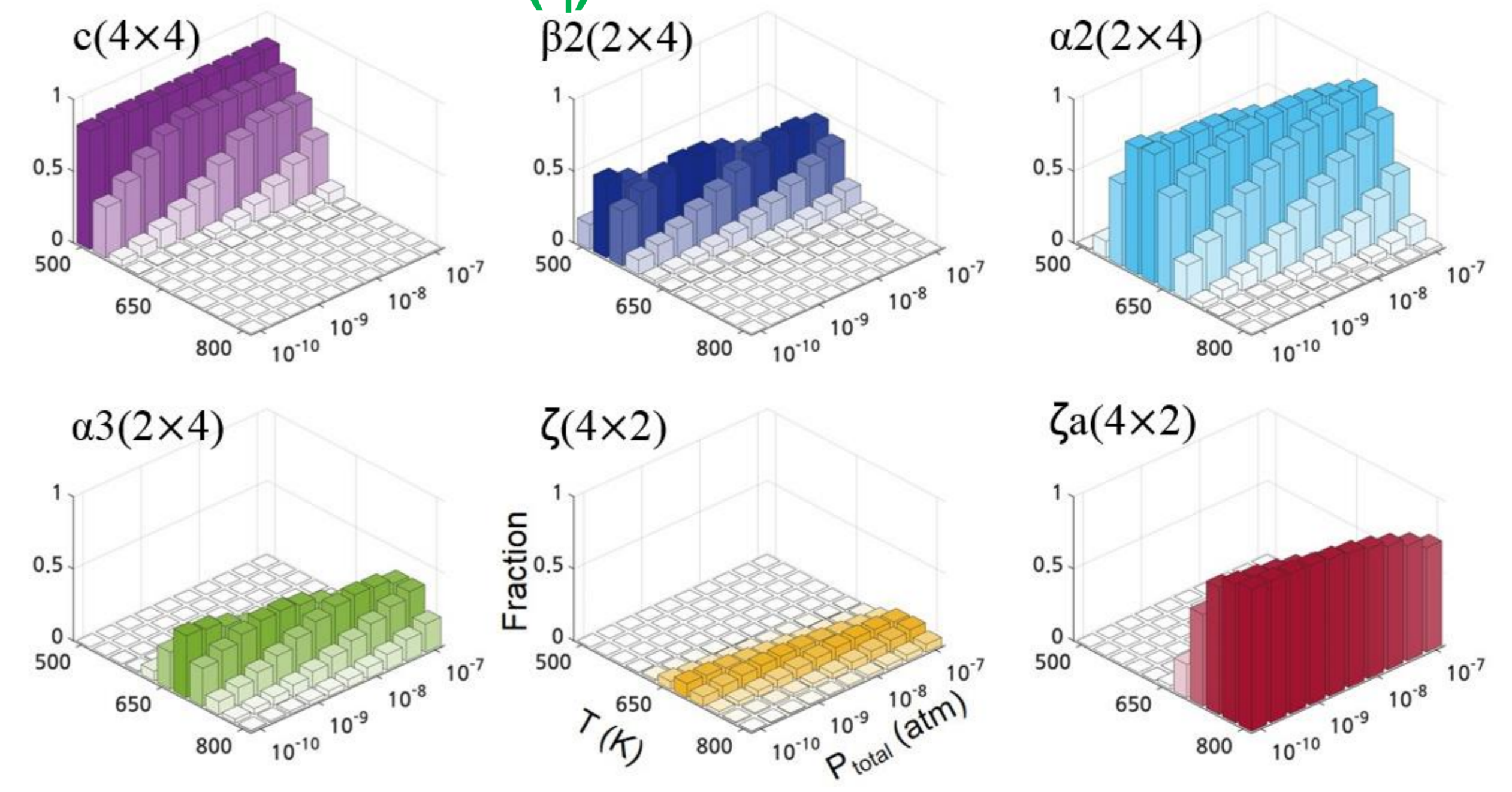
Consider Configuration entropy



$$\gamma_{(100)} = \sum_i \gamma_i \times f_i \text{ where } i \in \{100\} \text{ reconstructions}$$

$$\gamma_{(110)}, \gamma_{(111)A}, \gamma_{(111)B} = \dots$$

Fraction(f_i) of each reconstructions



Summary

Calculations of γ , μ , and S_{conf} enable to predict the surface structures & morphology as a function of (T,P).